Supplementary Information

Tunable type-II lateral MoSi₂N₄/WSi₂N₄ heterostructures for

photocatalytic applications

Wanxin Zhou^{1#}, Xingchen Zhou^{1#}, Cuihong Yang¹, Jingyun Zhang¹, Lu Wang¹, Qingfang Li^{1,2,3*} ¹School of Physics & Optoelectronic Engineering, Nanjing University of Information Science

and Technology, Nanjing 210044, People's Republic of China

²Jiangsu Key Laboratory for Optoelectronic Detection of Atmosphere and Ocean, Nanjing University of Information Science & Technology, Nanjing 210044, China

³Jiangsu International Joint Laboratory on Meteorological Photonics and Optoelectronic Detection, Nanjing University of Information Science & Technology, Nanjing 210044, China

The first two authors contributed equally to this investigation

Table I. The detailed information about crystal structure in $(MoSi_2N_4)_m(WSi_2N_4)_n$ lateral HSs with different widths. The w, a, h and S are the width, lattice constant, thickness and contact area of lateral HSs, respectively.

m(n)	w (Å)	a (Å)	h (Å)	S (Å ²)
4(4)	10.563	5.029	7.060	35.504
5(5)	13.479	5.033	7.068	35.575
6(6)	16.396	5.035	7.071	35.603
7(7)	19.304	5.036	7.073	35.622
8(8)	22.216	5.038	7.073	35.630



Fig. S1. Band structure of (MoSi₂N₄)₄(WSi₂N₄)₄ lateral heterostructure based on HSE



Fig. S2. Band structure and PDOS of (MoSi₂N₄)₅(WSi₂N₄)₅ based on PBE+SOC.



Fig. S3. The density of states of d orbitals of Mo/W in the (a) $MoSi_2N_4$, (b) $MoSi_2N_4$ and (c) $(MoSi_2N_4)_8(WSi_2N_4)_8$ lateral HSs.



Fig. S4. The band alignments of (a) $(MoSi_2N_4)_m(WSi_2N_4)_n$ (m+n=16) with the different component ratios, (b) $(MoSi_2N_4)_8(WSi_2N_4)_8$ lateral HSs with the different strains.